Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8	MOSDEN-A-.in. MOSDEN-.in. MOSDEN-AELAN-.in. PHAN-DUNG-.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:47
L2	2	("6316167").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/09/07 15:49
L3	12465	hard near mask hard-mask	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:51
L4	829863	resist photo-resist photoresist photosensitive photo-sensitive light-sensitive (sensitive near (photo light energy radiation))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:52
L5	119367	oxygen-contain$3 (o2 "o.sub.2" oxygen) near (plasma contain$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:59
L10	7336	5 near3 (expos$3 treat$3 modif$5 alter$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:29
L11	9	3 near3 10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:22
L12	58	5 with (expos$3 treat$3 modif$5 alter$3) with 3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:14
L13	49	12 not 11	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:19
L14	2	("20050039681").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/09/07 16:20

L16	44832	antireflective antireflection anti-reflective anti-reflection anti adj reflective anti adj reflection	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:21
L17	77775	organosilicon organometallic organo-silicon organo-metallic organo adj silicon organo adj metallic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:22
L18	48	(16 17) near3 10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:28
L19	4	4 with 18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:24
L21	8	4 same 18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:25
L22	57	(3 16 17) near3 10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:28
L23	6450	(3 16 17) near3 (expos$3 treat$3 modif$5 alter$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:29
L24	33	(3 16 17) near3 (expos$3 treat$3) near3 (chang$5 modif$5 alter$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:34
L25	19	(3 16 17) near3 (plasma) near3 (chang$5 modif$5 alter$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 16:34
L29	25	(plasma near oxidation) with (conventional$3 typical$3 known) with temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:40

L30	352	4 with ash$3 with (known conventional$3 typical$3) with 5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:42
L31	35	4 near3 ash$3 near3 (known conventional$3 typical$3) near3 5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:45
L32	3	3 near2 (alter$5 chang$3 modif$7) near2 surface	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:46
L33	133	(16 17) near2 (alter$5 chang$3 modif$7) near2 surface	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:59
L34	4	(17) near2 (alter$5 chang$3 modif$7) near2 5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 17:59
L35	119367	(oxygen-contain$3 near2 plasma) (o2 "o.sub.2" oxygen) near (plasma contain$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 18:00
L36	3068	17 near2 (layer film coating)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 18:00
L37	51	35 with 36	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 18:00